

IN THE UNITED STATES PATENT AND TRADEMARK OFFICE

In re Patent Application of : Docket: Y0R920000344US1
Jack O. Chu et al. : Group Art Unit: 2813
Serial No.: 09/692,606 : Examiner: E. Kielin
Filed: October 19, 2000 : Date: October 26, 2001

For: Layer Transfer of Low Defect SiGe Using an Etch-back Process



Election/Restriction Under 37CFR 1.141

Commissioner for Patents
Washington, D.C. 20231

Sir:

In response to the Requirement for Restriction under 35 U.S.C. 121, Applicant's elect, Group I, Species A which includes claims 1, 6, 9, 10 and 18-23, drawn to a method of preparing a Si/SiGe layer on a semiconductor substrate, classified in class 438, subclass 459.

Group I, Species B-E which includes claims 2-5, 7, 8, 11-17 and 24-30 are non elected.

The claims in Group II, Claims 31 - 42, drawn to a multilayer substrate, classified in class 428, subclass 428; are non elected.

Further favorable action and allowance of the claims is earnestly requested.

Respectfully submitted,
Attorney for the Applicant(s)

by


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